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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/612,174	07/02/2003	Robert K. Reich	MIT8806L	5221
75	90 01/27/2005		EXAM	INER
Theresa A. Lober			QUINTO, KEVIN V	
T.A. Lober Patent Services 45 Walden Street			ART UNIT	PAPER NUMBER
Concord, MA 01742			2826	
			DATE MAILED: 01/27/2005	

Please find below and/or attached an Office communication concerning this application or proceeding.

		Application No.	Applicant(s)			
Office Action Summary		10/612,174	REICH ET AL.			
		Examiner	Art Unit			
		Kevin Quinto	2826			
Period fo	The MAILING DATE of this communication appears on the cover sheet with the correspondence address Period for Reply					
THE - Exte after - If the - If NO - Faile Any	ORTENED STATUTORY PERIOD FOR REPLY MAILING DATE OF THIS COMMUNICATION. Insions of time may be available under the provisions of 37 CFR 1.13 SIX (6) MONTHS from the mailing date of this communication. In period for reply specified above is less than thirty (30) days, a reply of period for reply is specified above, the maximum statutory period were to reply within the set or extended period for reply will, by statute, reply received by the Office later than three months after the mailing ed patent term adjustment. See 37 CFR 1.704(b).	36(a). In no event, however, may a reply be ting within the statutory minimum of thirty (30) day vill apply and will expire SIX (6) MONTHS from a cause the application to become ABANDONE	nely filed s will be considered timely. the mailing date of this communication. D (35 U.S.C. § 133).			
Status						
1)⊠	Responsive to communication(s) filed on 01 November 2004.					
2a)□	This action is FINAL . 2b)⊠ This	action is non-final.				
3)[Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under <i>Ex parte Quayle</i> , 1935 C.D. 11, 453 O.G. 213.					
Disposit	ion of Claims					
	4)⊠ Claim(s) <u>1-24</u> is/are pending in the application.					
• / كـــــــــــــــــــــــــــــــــــ	4a) Of the above claim(s) is/are withdrawn from consideration.					
5)	Claim(s) is/are allowed.					
·	Claim(s) 1-24 is/are rejected.					
7)						
8) Claim(s) are subject to restriction and/or election requirement.						
Applicat	ion Papers					
9) The specification is objected to by the Examiner.						
	10) The drawing(s) filed on is/are: a) accepted or b) objected to by the Examiner.					
	Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).					
	Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).					
11)	11)☐ The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.					
Priority (under 35 U.S.C. § 119					
	Acknowledgment is made of a claim for foreign All b) Some * c) None of: 1. Certified copies of the priority documents 2. Certified copies of the priority documents	s have been received.				
	3. Copies of the certified copies of the prior application from the International Bureau	ity documents have been receive				
* See the attached detailed Office action for a list of the certified copies not received.						
Attachmen	t(s)	_				
1) Notice of References Cited (PTO-892) 4) Interview Summary (PTO-413) 2) Notice of Draftsperson's Patent Drawing Review (PTO-948) Paper No(s)/Mail Date.						
	e of Draftsperson's Patent Drawing Review (PTO-948) mation Disclosure Statement(s) (PTO-1449 or PTO/SB/08)		ate Patent Application (PTO-152)			
Paper No(s)/Mail Date <u>1 November 2004</u> . 6) ☐ Other:						

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DETAILED ACTION

Response to Arguments

- 1. Applicant's arguments with respect to claims 1-24 have been considered but are moot in view of the new ground(s) of rejection.
- 2. In light of the amendment made to the title, the examiner hereby withdraws the objection made to the specification in the previous Office action.

Claim Rejections - 35 USC § 102

3. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

- (e) the invention was described in (1) an application for patent, published under section 122(b), by another filed in the United States before the invention by the applicant for patent or (2) a patent granted on an application for patent by another filed in the United States before the invention by the applicant for patent, except that an international application filed under the treaty defined in section 351(a) shall have the effects for purposes of this subsection of an application filed in the United States only if the international application designated the United States and was published under Article 21(2) of such treaty in the English language.
- 4. Claims 1-24 are rejected under 35 U.S.C. 102(e) as being anticipated by Reich et al. ("High-Fill-Factor, Burst-Frame-Rate Charge-coupled Device," International Electron Device Meeting and IEDM Technical Digest, pp. 567-570, December 2001).
- 5. In reference to claims 1 and 9, Reich et al. ("High-Fill-Factor, Burst-Frame-Rate Charge-coupled Device," International Electron Device Meeting and IEDM Technical Digest, pp. 567-570, December 2001, hereinafter referred to as the "Reich" reference) discloses a similar charge-coupled imager for imaging a sequence of image frames. Figure 2 of Reich illustrates an array of super pixels disposed in a semiconductor

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substrate having a surface that is accessible to incident illumination. Each super pixel has a plurality of independently-controlled subpixels . The control electrode comprises three electrodes which correspond to three-phase photogenerated charge collection. Reich discloses the use of a subpixel which utilizes a doped charge collection control layer in the substrate (p. 569, which refers to using the charge collection control layer disclosed in Reich et al., "Integrated Electronic Shutter for Back-Illuminated Chargecoupled Devices," IEEE Transactions on Electron Devices, Vol. 40, No. 7, pp. 1231-1237, July 1993, hereinafter referred to as the "Reich 93" reference). Reich 93 discloses a CCD which utilizes a doped charge collection control layer in the substrate. Figures 1(a)-1(b) of Reich 93 show a CCD with a doped photogenerated charge collection channel region which is opposite the illumination accessible substrate surface. There is a charge collection channel region control electrode. The control electrode comprises three electrodes which correspond to three-phase photogenerated charge collection. Doped charge drain regions are adjacent to the channel region. There is also a charge drain region control electrode. There is a doped charge collection control layer in the substrate below the charge collection channel region. The charge collection channel region, the charge drain regions, and the charge collection control layer are each characterized by a dopant type and its concentration for expanding the charge collection channel region in response to a charge collection control voltage applied to the channel region control electrode in order to collect in the charge collection channel region photogenerated charge during its designated image frame. Furthermore the charge collection channel region contracts in response to a

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charge storage control voltage applied to the channel region control electrode in order to store the collected photogenerated charge in the charge collection channel region and collect substantially no additional photogenerated charge.

- 6. With regard to claims 2 and 3, Reich 93 discloses the use of a p⁻ substrate, an n-type charge collection channel region, n⁺ charge drain regions, and a p⁺ charge collection control layer.
- 7. In reference to claim 4, the charge collection channel region comprises a buried channel disposed adjacent to a substrate surface opposite the illumination-accessible substrate surface.
- 8. With regard to claim 5, the charge collection control layer includes first sections that are at a first depth in the substrate and located under a first section of the charge collection channel region and all of the charge drain regions. The charge collection control layer includes second sections that are at a second depth in the substrate different from the first depth and located under a second section of the charge collection channel region.
- 9. In reference to claims 6 and 7, figure 4(a) of Reich 93 shows that charge collection control voltage is selected to expand a depletion region of the charge collection channel region into the substrate to a depth greater than the depth of the charge collection control layer. In addition, figure 4(b) of Reich 93 shows that charge collection control voltage is selected to contract a depletion region of the charge collection channel region into the substrate to a depth less than the depth of the charge collection control layer.

- 10. With regard to claim 8, the illumination-accessible substrate surface is a back side of the substrate while the control electrodes are disposed on the front side of the substrate.
- 11. In reference to claim 10 and 15, Reich ("High-Fill-Factor, Burst-Frame-Rate Charge-coupled Device," International Electron Device Meeting and IEDM Technical Digest, pp. 567-570, December 2001) discloses a similar charge-coupled imager for imaging a sequence of image frames. Figure 2 of Reich illustrates an array of super pixels disposed in a semiconductor substrate having a surface that is accessible to incident illumination. Each super pixel has a plurality of independently-controlled subpixels. The control electrode comprises three electrodes which correspond to threephase photogenerated charge collection. Reich discloses the use of a subpixel which utilizes a doped charge collection control layer in the substrate (p. 569, which refers to using the charge collection control layer disclosed in Reich 93, "Integrated Electronic Shutter for Back-Illuminated Charge-coupled Devices," IEEE Transactions on Electron Devices, Vol. 40, No. 7, pp. 1231-1237, July 1993). Reich 93 discloses a CCD which utilizes a doped charge collection control layer in the substrate. Figures 1(a)-1(b) of Reich 93 show a CCD with a doped photogenerated charge collection channel region which is opposite the illumination accessible substrate surface. There is a charge collection channel region control electrode. Doped charge drain regions are adjacent to the channel region. There is also a charge drain region control electrode. There is a doped charge collection control layer in the substrate below the charge collection channel region. The charge collection channel region, the charge drain regions, and the

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charge collection control layer are each characterized by a dopant type and its concentration for expanding the charge collection channel region in response to a charge collection control voltage applied to the channel region control electrode in order to collect in the charge collection channel region photogenerated charge during its designated image frame. Furthermore the charge collection channel region contracts in response to a charge storage control voltage applied to the channel region control electrode in order to store the collected photogenerated charge in the charge collection channel region. Each device has a channel region control voltage connection on a substrate surface opposite the illumination-accessible surface which is configured for independent collection and storage of photogenerated charge from the substrate at the charge collection channel region.

- 12. In reference to claim 11, Reich 93 shows that a drain region control voltage collection is provided to each device or subpixel opposite the illumination accessible surface. The drain region control voltage collection can be configured for drainage of photogenerated charge from the substrate to a subpixel drain region in response to a drain region control signal.
- 13. In reference to claims 12 and 13, the Reich 93 device has a channel region control voltage which can be configured for collection and storage of photogenerated charge from the substrate at the charge collection channel region. Furthermore, the channel region control voltage can be configured for subpixel-specific weighting of collection and storage of photogenerated charge from the substrate at each subpixel.

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Reich shows that at least two subpixels are functioning during a corresponding frame in figure 3.

- 14. With regard to claim 14, the Reich 93 device has a channel region control voltage collection which can be configured for control of the correspondence between the subpixels and the image frames.
- 15. With reference to claim 16, Reich discloses the use of metal for the control signal lines (p. 568) in figure 2.
- 16. In reference to claim 17, figure 2 of Reich illustrates the use of semiconducting isolation lines between the control signal lines, the charge collection channel region control electrodes, and the drain control electrodes.
- 17. In reference to claims 18-20, figure 1 of Reich discloses the use of a serial output register and a column binning register in the substrate to accept a sequence of image frame charge from each super pixel after the image frame sequence is collected and stored at each super pixel.
- 18. In reference to claims 21-24, Reich ("High-Fill-Factor, Burst-Frame-Rate Charge-coupled Device," International Electron Device Meeting and IEDM Technical Digest, pp. 567-570, December 2001) discloses a similar charge-coupled imager for imaging a sequence of image frames. Figure 2 of Reich illustrates an array of super pixels disposed in a semiconductor substrate having a surface that is accessible to incident illumination. Each super pixel has a plurality of independently-controlled subpixels. The control electrode comprises three electrodes which correspond to three-phase photogenerated charge collection. The number of subpixels included in each super

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pixel are selected based on the length of the image frame sequence and image rate. In addition, the subpixels collect and store at the super pixel each frame of the image frame sequence before transferring the image frame sequence from the super pixel. Figure 3 of Reich shows that at least two subpixels are functioning during a corresponding frame. Reich discloses the use of a subpixel which utilizes a doped charge collection control layer in the substrate (p. 569, which refers to using the charge collection control layer disclosed in Reich 93, "Integrated Electronic Shutter for Back-Illuminated Charge-coupled Devices," IEEE Transactions on Electron Devices, Vol. 40, No. 7, pp. 1231-1237, July 1993). Reich 93 discloses a CCD which utilizes a doped charge collection control layer in the substrate. Figures 1(a)-1(b) of Reich 93 show a CCD with a doped photogenerated charge collection channel region which is opposite the illumination accessible substrate surface. There is a charge collection channel region control electrode. Doped charge drain regions are adjacent to the channel region. There is also a charge drain region control electrode. There is a doped charge collection control region in the substrate below the charge collection channel region.

Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Kevin Quinto whose telephone number is (571) 272-1920. The examiner can normally be reached on M-F 8AM-5PM.

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If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Nathan Flynn can be reached on (571) 272-1915. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

KVQ

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